

# Session JJ

## On-Wafer and Noise Measurements

**Chairman:**

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On-wafer and noise measurements have become very common place in the microwave semiconductor community. This session is composed of papers that demonstrate the advances in the state-of-the-art in noise measurements as well as on-wafer probing techniques. The papers include a novel noise parameter extraction technique and noise model verification based on noise and S-parameter measurements. New analysis and calibration procedures are introduced that solve some of the traditional problems in on-wafer calibrations and measurements. The feasibility of V-band on-wafer measurements is demonstrated with the use of a ridge-trough waveguide probe. Non-contacting probing techniques are discussed that yield accurate phase and amplitude electrooptic measurements as well as accurate microwave resistivity measurements from a millimeter waveguide probe. This session should be of major interest to engineers who are pursuing the state-of-the-art in on-wafer and noise measurements.

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**10:30 a.m.–12:00 p.m., Thursday, June 13, 1991  
Room 302**